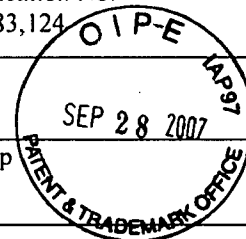


FORM PTO-1449

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Bernd SZYSKA et al.Filing Date
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
/RM/	4 8 6 6 0 3 2	09/12/89	FUJIMORI et al.			
/RM/	5 5 5 8 7 5 0	09/24/96	SZCZYRBOWSKI			
/RM/	5 3 8 4 0 2 1	01/24/95	THWAITES			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
/RM/	0 2 9 1 0 4 4	11/17/88	E.P.O.			
/RM/	4 4 1 8 9 0 6	12/07/95	GERMANY			
/RM/	0 5 3 7 0 1 1	04/14/93	E.P.O.			
/RM/	1 2 3 2 2 9 3	08/21/02	E.P.O.			
/RM/	0 7 9 5 6 2 3	09/17/97	E.P.O.			

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EXAMINER /Rodney McDonald/

DATE CONSIDERED 11/10/2008

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.